FUJIFILM

WNRD

Waycoat Negative Resist Developer

Product description

Waycoat Negative Resist Developer (WNRD) is a xylene free developer for polyisoprene based negative resists. Suitable for use with track or tank equipment.

Product benefits

* WNRD does not contain xylene, thereby reducing resist swelling during develop. As a result the incidence of fine bridging (webbing) is reduced, leading to cleaner development of small geometries.

* The trace element content of WNRD is very low, thus meeting today's production requirements.

Technical data

Specific Gravity (@ 20°C)		0.74 to 0.76 ml	
Non Volatile residue:		30 ppm	
Purity:	Al = 50 ppb,	Ca = 50 ppb,	Cu = 50 ppb,
	Cr = 50 ppb,	Fe = 50 ppb,	Mg = 50 ppb,
	Ni = 50 ppb,	Na = 50 ppb,	K = 50 ppb,
	Zn = 50 ppb		
Water Content:		= 100 ppm	
Avg Particles (> 0.5µm)		= 50 p/ml	

FUJIFILM Electronic Materials' resist products are subjected to state of the art measurements to ensure consistent performance and purity. Certificates of Analysis for each production batch are available. These certificates indicate some of the tests carried out and the results obtained.

Additional information

Unit Size : Waycoat Negative resist Developer is packaged in a unit size of 4 x 5 liters bottles or 200 liters drums.

Storage : It is recommended that WNRD is stored in a temperature controlled area to prevent freezing or prolonged exposure to temperatures above 30°C.

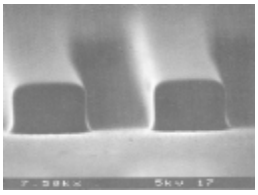
Shelf life : Two years from date of manufacture, if stored between 10 and 30°C in the original sealed container.

Safety : It is recommended that WNRD is not stored in close proximity to strong acids or ammonium compounds.
Adequate ventilation during developing is necessary to maintain vapor concentration within acceptable limits. Use only in strict accordance to our facilities safety requirements.
Material Safety Data Sheets are available to the user from any FUJIFILM Electronic Materials location.

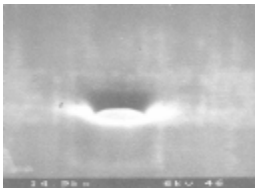
Compatibility: Waycoat Negative Resist Developer is compatible with most commercially available develop processing equipment.
Compatible materials include stainless steel, glass, quartz and teflon.

Results obtained

Using the track process with a CANON PLA 521 F the following results were obtained:



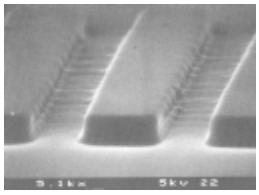
Lines and spaces,
printed in 3µ thick SC-180, developed in WNRD.



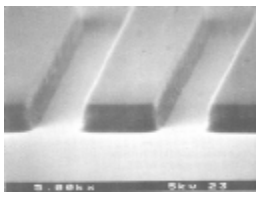
Contact hole,
printed in 0.9µ thick HNR 120, developed in WNRD.

Improved results

The photographs below compare results obtained with WNRD and a xylene based developer.



Lines and spaces,
contact printed in 3µ thick SC-180, developed in xylene.



Lines and spaces.
contact printed in 3µ thick SC-180, developed in WNRD.